



Special Issue on

## **Nanofabrication, Atomic and Close-to-atomic Scale Manufacturing**

### **Guest Editors:**

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### **Scope of this special issue**

Papers in all areas of nanofabrication and atomic and close-to-atomic scale manufacturing (ACSM) technologies will be considered, including but not limited to:

- Lithography technologies (extreme ultraviolet, electron beam, focused ion beam, nanoimprint, etc.)
- Ultra-precision diamond turning/milling/grinding
- Ultra-precision polishing (ion/plasma/RAPT/MRF/EEM/CMP/Fluid jet, etc.)
- Ultrafast laser machining
- Directed self-assembly
- Nano 3D printing
- Atomic layer deposition
- AFM tip-based nanomachining and lithography technologies
- STM atomic manipulation
- Modelling and simulation technologies for nanofabrication and ACSM

- Test-bed/machines for nanofabrication and ACSM
- Metrology technologies/devices/instruments for nanofabrication and ACSM

Original research papers, review articles and short communications are all welcome

All manuscripts must be submitted through the manuscripts system at

<https://www.editorialmanager.com/nmme/default.aspx>

**Submission Deadline:** 15 June 2020

**Publication Date:** September 2020